

# PATENT ABSTRACTS OF JAPAN

(11)Publication number : 2003-215309

(43)Date of publication of application : 30.07.2003

(51)Int.Cl.

G02B 1/11  
B32B 7/02  
B32B 9/00  
C23C 14/08  
G02B 1/10

(21)Application number : 2002-074033

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(22)Date of filing : 18.03.2002

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(30)Priority

Priority number : 2001118463 Priority date : 17.04.2001 Priority country : JP

2001353265 19.11.2001

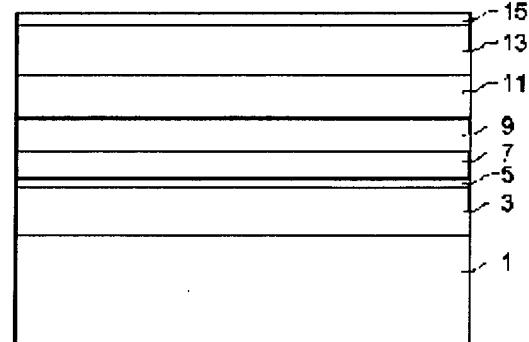
JP

## (54) ANTIREFLECTION FILM AND ANTIREFLECTION LAYER-AFFIXED PLASTIC SUBSTRATE

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a colorless antireflection film excellent in productivity and high in transparency, and an antireflection layer-affixed plastic substrate and to provide an antireflection film and an antireflection layer-affixed plastic substrate having moisture-proofing and gas-barrier properties and being excellent in optical characteristics.

SOLUTION: An antireflection film is provided which comprises a hard coat layer formed on a substrate, and a transparent, high-refractive-index oxide layer and a transparent, low-refractive-index oxide layer alternately laminated on the hard coat layer. The transparent, high-refractive-index oxide layer is composed of an Nb<sub>2</sub>O<sub>5</sub> layer formed by a reactive sputtering method. In an antireflection film using a substrate consisting of



1:ベース  
2:ハイドロコート層  
3:第1スピッタ層  
7:第1透明高屈折率酸化物層  
9:第1透明低屈折率酸化物層  
11:第2透明高屈折率酸化物層  
13:第2透明低屈折率酸化物層  
15:防汚層

- an organic material, an inorganic, moisture-proofing layer having a refractive index approximate to that of the organic material is formed in contact with one surface of the substrate.

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#### LEGAL STATUS

[Date of request for examination] 17.10.2002

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]